

STN-CAS Search  
Do Not Remove!

chain nodes :

6 7 8 9 10 11 12 13 14 15 16 17 18 19 20 21 22 23 27

ring nodes :

1 2 3 4 5

chain bonds :

3-6 6-7 7-8 8-9 9-10 9-18 9-27 10-11 11-12 11-17 12-13 13-14 13-15 13-16  
19-20 20-21 21-22

ring bonds :

1-2 1-5 2-3 3-4 4-5

exact/norm bonds :

1-2 1-5 2-3 3-4 3-6 4-5 6-7 9-18 9-27 11-12 11-17 12-13

exact bonds :

7-8 8-9 9-10 10-11 13-14 13-15 13-16 19-20 20-21 21-22

G1:[\*1],[\*2]

Match level :

1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:CLASS 7:CLASS 8:CLASS 9:CLASS 10:CLASS  
11:CLASS 12:CLASS 13:CLASS 14:CLASS 15:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS  
20:CLASS 21:CLASS 22:CLASS 23:CLASS 27:CLASS

L2 ANSWER 1 OF 422 REGISTRY COPYRIGHT 2003 ACS  
RN 508693-53-6 REGISTRY  
CN **Gamma-butyrolactone receptor protein (Streptomyces avermitilis strain MA-4680 gene avaR) (9CI) (CA INDEX NAME)**

OTHER NAMES:

CN GenBank BAC71417  
CN GenBank BAC71417 (Translated from: GenBank AP005036)  
FS PROTEIN SEQUENCE  
MF Unspecified  
CI MAN  
SR GenBank  
LC STN Files: CA, CAPLUS

\*\*\* STRUCTURE DIAGRAM IS NOT AVAILABLE \*\*\*

\*\*\* USE 'SQD' OR 'SQIDE' FORMATS TO DISPLAY SEQUENCE \*\*\*

1 REFERENCES IN FILE CA (1957 TO DATE)

1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> d his

(FILE 'HOME' ENTERED AT 15:58:22 ON 10 JUN 2003)

FILE 'REGISTRY' ENTERED AT 15:58:43 ON 10 JUN 2003

L1 0 S GAMMA-BUTROLACTONE  
L2 422 S GAMMA-BUTYROLACTONE

=> d 1

L2 ANSWER 1 OF 422 REGISTRY COPYRIGHT 2003 ACS  
RN 508693-53-6 REGISTRY  
CN **Gamma-butyrolactone receptor protein (Streptomyces avermitilis strain MA-4680 gene avaR) (9CI) (CA INDEX NAME)**

OTHER NAMES:

CN GenBank BAC71417  
CN GenBank BAC71417 (Translated from: GenBank AP005036)  
FS PROTEIN SEQUENCE  
MF Unspecified  
CI MAN  
SR GenBank  
LC STN Files: CA, CAPLUS

\*\*\* STRUCTURE DIAGRAM IS NOT AVAILABLE \*\*\*

\*\*\* USE 'SQD' OR 'SQIDE' FORMATS TO DISPLAY SEQUENCE \*\*\*

1 REFERENCES IN FILE CA (1957 TO DATE)

1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> d 5

L2 ANSWER 5 OF 422 REGISTRY COPYRIGHT 2003 ACS  
RN 499203-67-7 REGISTRY  
CN 2-Propenoic acid, 2-methyl-, 2-hydroxypropyl ester, polymer with phenylmethyl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

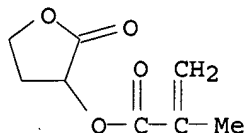
OTHER NAMES:

CN **Benzyl methacrylate-2-hydroxypropyl methacrylate-.alpha.-methacryloyloxy-.gamma.-butyrolactone copolymer**  
MF (C11 H12 O2 . C8 H10 O4 . C7 H12 O3)x  
CI PMS  
PCT Polyacrylic, Polyester, Polyester formed  
SR CA  
LC STN Files: CA, CAPLUS

CM 1

CRN 195000-66-9

CMF C8 H10 O4

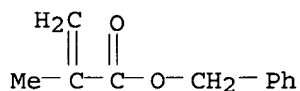


*δ-butyrolactone  
methacrylate*

CM 2

CRN 2495-37-6

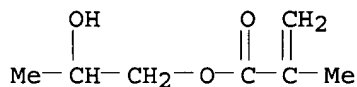
CMF C11 H12 O2



CM 3

CRN 923-26-2

CMF C7 H12 O3



2 REFERENCES IN FILE CA (1957 TO DATE)

2 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> FILE REG

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

24.80

25.01

FILE 'REGISTRY' ENTERED AT 16:00:16 ON 10 JUN 2003

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

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STRUCTURE FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8

DICTIONARY FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 6, 2003

Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. See HELP PROPERTIES for more information. See STNote 27, Searching Properties in the CAS Registry File, for complete details:  
<http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf>

=> STR 195000-66-9

:END

L3 STRUCTURE CREATED

=> S L3 EXA SAM

SAMPLE SEARCH INITIATED 16:00:20 FILE 'REGISTRY'  
SAMPLE SCREEN SEARCH COMPLETED - 0 TO ITERATE

100.0% PROCESSED 0 ITERATIONS 0 ANSWERS  
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*  
PROJECTED ITERATIONS: 0 TO 0  
PROJECTED ANSWERS: 0 TO 0

L4 0 SEA EXA SAM L3

=>

=>

NO ANSWERS WERE FOUND

=> FIL REGISTRY

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.40	25.41

FILE 'REGISTRY' ENTERED AT 16:00:32 ON 10 JUN 2003  
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STRUCTURE FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8  
DICTIONARY FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8

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<http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf>

=> S 195000-66-9/RN

L5 1 195000-66-9/RN

=> SET NOTICE 1 DISPLAY

NOTICE SET TO 1 U.S. DOLLAR FOR DISPLAY COMMAND  
SET COMMAND COMPLETED

=> D L5 RN CCN 1-

YOU HAVE REQUESTED DATA FROM 1 ANSWERS - CONTINUE? Y/(N):y  
THE ESTIMATED COST FOR THIS REQUEST IS 1.68 U.S. DOLLARS  
DO YOU WANT TO CONTINUE WITH THIS REQUEST? (Y)/N:y

L5 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2003 ACS  
RN 195000-66-9 REGISTRY  
CN 2-Propenoic acid, 2-methyl-, tetrahydro-2-oxo-3-furanyl ester (9CI) (CA  
INDEX NAME)  
OTHER NAMES:  
CN .alpha.-Methacryloyloxy-.gamma.-butyrolactone

=> SET NOTICE LOGIN DISPLAY

NOTICE SET TO OFF FOR DISPLAY COMMAND  
SET COMMAND COMPLETED

=>

=> d l1 d9

L1 HAS NO ANSWERS

L1 0 SEA FILE=REGISTRY ABB=ON PLU=ON GAMMA-BUTROLACTONE

=> d his

(FILE 'HOME' ENTERED AT 15:58:22 ON 10 JUN 2003)

FILE 'REGISTRY' ENTERED AT 15:58:43 ON 10 JUN 2003

L1 0 S GAMMA-BUTROLACTONE  
L2 422 S GAMMA-BUTYROLACTONE

FILE 'REGISTRY' ENTERED AT 16:00:16 ON 10 JUN 2003

L3 STR 195000-66-9  
L4 0 S L3 EXA SAM

FILE 'REGISTRY' ENTERED AT 16:00:32 ON 10 JUN 2003

L5 1 S 195000-66-9/RN  
SET NOTICE 1 DISPLAY  
SET NOTICE LOGIN DISPLAY

=> file reg

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	2.48	27.89

FILE 'REGISTRY' ENTERED AT 16:01:26 ON 10 JUN 2003  
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STRUCTURE FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8  
DICTIONARY FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 6, 2003

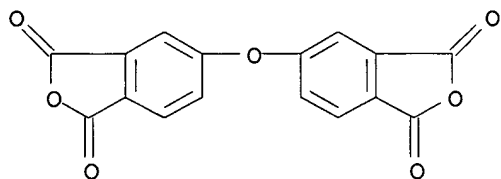
Please note that search-term pricing does apply when  
conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

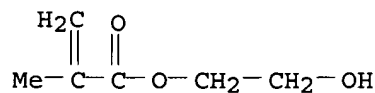
Experimental and calculated property data are now available. See HELP  
PROPERTIES for more information. See STNote 27, Searching Properties  
in the CAS Registry File, for complete details:  
<http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf>

=> d'12 10

L2 ANSWER 10 OF 422 REGISTRY COPYRIGHT 2003 ACS  
RN 469897-99-2 REGISTRY  
CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with  
1H,3H-benzo[1,2-c:4,5-c']difuran-1,3,5,7-tetrone, dihydro-2(3H)-furanone,  
4,4'-oxybis[benzenamine] and 5,5'-oxybis[1,3-isobenzofurandione] (9CI)  
(CA INDEX NAME)  
OTHER NAMES:  
CN **.gamma.-Butyrolactone-4,4'-diaminodiphenyl ether-3,3',4,4'-diphenyl  
ether tetracarboxylic acid dianhydride-2-hydroxyethyl methacrylate-  
pyromellitic anhydride copolymer**  
MF (C16 H6 O7 . C12 H12 N2 O . C10 H2 O6 . C6 H10 O3 . C4 H6 O2)x  
CI PMS  
PCT Polyacrylic, Polyamic acid, Polyamic acid formed, Polyester, Polyester  
formed, Polyether, Polyimide, Polyimide formed  
SR CA  
LC STN Files: CA, CAPLUS  
  
CM 1  
  
CRN 1823-59-2  
CMF C16 H6 O7

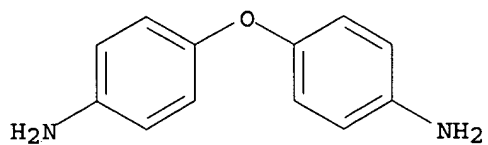


CM 2  
  
CRN 868-77-9  
CMF C6 H10 O3



CM 3  
  
CRN 101-80-4

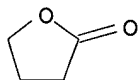
CMF C12 H12 N2 O



CM 4

CRN 96-48-0

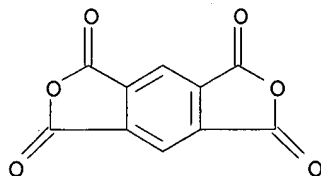
CMF C4 H6 O2



CM 5

CRN 89-32-7

CMF C10 H2 O6



1 REFERENCES IN FILE CA (1957 TO DATE)

1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> d 12 3

L2 ANSWER 3 OF 422 REGISTRY COPYRIGHT 2003 ACS

RN 501948-09-0 REGISTRY

CN Carbamic acid, [[[2S]-tetrahydro-5-oxo-2-furanyl]methyl]-, phenylmethyl ester (9CI) (CA INDEX NAME)

OTHER NAMES:

CN N-(Benzyloxycarbonyl)-.gamma.-aminomethyl-.gamma.-butyrolactone

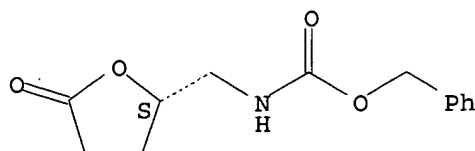
FS STEREOSEARCH

MF C13 H15 N O4

SR CA

LC STN Files: CA, CAPLUS, CASREACT

Absolute stereochemistry.



**\*\*PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT\*\***

1 REFERENCES IN FILE CA (1957 TO DATE)  
1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> file reg		
COST IN U.S. DOLLARS	SINCE FILE	TOTAL
	ENTRY	SESSION
FULL ESTIMATED COST	3.76	31.65

FILE 'REGISTRY' ENTERED AT 16:02:03 ON 10 JUN 2003  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
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STRUCTURE FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8  
DICTIONARY FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 6, 2003

Please note that search-term pricing does apply when  
conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. See HELP  
PROPERTIES for more information. See STNote 27, Searching Properties  
in the CAS Registry File, for complete details:  
<http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf>

=> s gamma-butyrolactone methacrylate  
118094 GAMMA  
1 GAMMAS  
118094 GAMMA  
(GAMMA OR GAMMAS)  
631 BUTYROLACTONE  
39272 METHACRYLATE  
10 METHACRYLATES  
39272 METHACRYLATE  
(METHACRYLATE OR METHACRYLATES)  
L6 2 GAMMA-BUTYROLACTONE METHACRYLATE  
(GAMMA (W) BUTYROLACTONE (W) METHACRYLATE)

=> d

L6 ANSWER 1 OF 2 REGISTRY COPYRIGHT 2003 ACS  
RN 195000-67-0 REGISTRY  
CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl ester,  
polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA  
INDEX NAME)  
OTHER CA INDEX NAMES:  
CN 2-Propenoic acid, 2-methyl-, tetrahydro-2-oxo-3-furanyl ester, polymer  
with 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl 2-methyl-2-propenoate (9CI)  
OTHER NAMES:  
CN .alpha.-Methacryloyloxy-.gamma.-butyrolactone-2-methyl-2-adamantyl  
methacrylate copolymer  
CN .gamma.-Butyrolacton-2-yl methacrylate-2-methyl-2-adamantyl methacrylate  
copolymer  
CN .gamma.-Butyrolactone methacrylate-2-methyladamantyl methacrylate



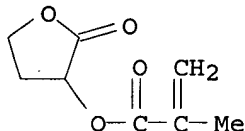
**copolymer**

DR 443892-48-6  
MF (C15 H22 O2 . C8 H10 O4)x  
CI PMS  
PCT Polyacrylic, Polyester, Polyester formed  
SR CA  
LC STN Files: CA, CAPLUS, TOXCENTER, USPATFULL

CM 1

CRN 195000-66-9

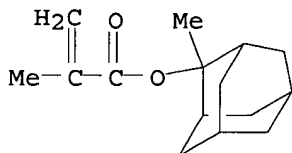
CMF C8 H10 O4



CM 2

CRN 177080-67-0

CMF C15 H22 O2



42 REFERENCES IN FILE CA (1957 TO DATE)  
42 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> s 2-methyladamantyl methacrylate

15320244 2

18 METHYLADAMANTYL

39272 METHACRYLATE

10 METHACRYLATES

39272 METHACRYLATE

(METHACRYLATE OR METHACRYLATES)

L7 7 2-METHYLADAMANTYL METHACRYLATE

(2 (W) METHYLADAMANTYL (W) METHACRYLATE)

=> d his

(FILE 'HOME' ENTERED AT 15:58:22 ON 10 JUN 2003)

FILE 'REGISTRY' ENTERED AT 15:58:43 ON 10 JUN 2003

L1 0 S GAMMA-BUTYROLACTONE

L2 422 S GAMMA-BUTYROLACTONE

FILE 'REGISTRY' ENTERED AT 16:00:16 ON 10 JUN 2003

L3 STR 195000-66-9

L4 0 S L3 EXA SAM

FILE 'REGISTRY' ENTERED AT 16:00:32 ON 10 JUN 2003

L5 1 S 195000-66-9/RN

SET NOTICE 1 DISPLAY  
SET NOTICE LOGIN DISPLAY

FILE 'REGISTRY' ENTERED AT 16:01:26 ON 10 JUN 2003

FILE 'REGISTRY' ENTERED AT 16:02:03 ON 10 JUN 2003

L6 2 S GAMMA-BUTYROLACTONE METHACRYLATE  
L7 7 S 2-METHYLADAMANTYL METHACRYLATE

=> s l6 and l7

L8 1 L6 AND L7

=> d l8

L8 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2003 ACS

RN 195000-67-0 REGISTRY

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl ester,  
polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA  
INDEX NAME)


OTHER CA INDEX NAMES:

CN 2-Propenoic acid, 2-methyl-, tetrahydro-2-oxo-3-furanyl ester, polymer  
with 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl 2-methyl-2-propenoate (9CI)

OTHER NAMES:

CN .alpha.-Methacryloyloxy-.gamma.-butyrolactone-2-methyl-2-adamantyl  
methacrylate copolymer

CN .gamma.-Butyrolacton-2-yl methacrylate-2-methyl-2-adamantyl methacrylate  
copolymer

CN **.gamma.-Butyrolactone methacrylate-2-methyladamantyl methacrylate**   
copolymer

DR 443892-48-6

MF (C15 H22 O2 . C8 H10 O4)x

CI PMS

PCT Polyacrylic, Polyester, Polyester formed

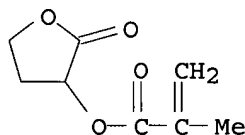
SR CA

LC STN Files: CA, CAPLUS, TOXCENTER, USPATFULL

CM 1

CRN 195000-66-9

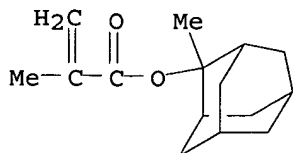
CMF C8 H10 O4



CM 2

CRN 177080-67-0

CMF C15 H22 O2



42 REFERENCES IN FILE CA (1957 TO DATE)  
42 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2  
COST IN U.S. DOLLARS

SINCE FILE	TOTAL
ENTRY	SESSION
29.48	61.13

FULL ESTIMATED COST

FILE 'CAPLUS' ENTERED AT 16:03:03 ON 10 JUN 2003  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
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FILE 'HCAPLUS' ENTERED AT 16:03:03 ON 10 JUN 2003  
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FILE 'USPATFULL' ENTERED AT 16:03:03 ON 10 JUN 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPAT2' ENTERED AT 16:03:03 ON 10 JUN 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> d his

(FILE 'HOME' ENTERED AT 15:58:22 ON 10 JUN 2003)

FILE 'REGISTRY' ENTERED AT 15:58:43 ON 10 JUN 2003

L1 0 S GAMMA-BUTYROLACTONE  
L2 422 S GAMMA-BUTYROLACTONE

FILE 'REGISTRY' ENTERED AT 16:00:16 ON 10 JUN 2003

L3 STR 195000-66-9  
L4 0 S L3 EXA SAM

FILE 'REGISTRY' ENTERED AT 16:00:32 ON 10 JUN 2003

L5 1 S 195000-66-9/RN  
SET NOTICE 1 DISPLAY  
SET NOTICE LOGIN DISPLAY

FILE 'REGISTRY' ENTERED AT 16:01:26 ON 10 JUN 2003

FILE 'REGISTRY' ENTERED AT 16:02:03 ON 10 JUN 2003

L6 2 S GAMMA-BUTYROLACTONE METHACRYLATE  
L7 7 S 2-METHYLADAMANTYL METHACRYLATE  
L8 1 S L6 AND L7

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 16:03:03 ON 10 JUN 2003

=> s l8

L9 95 L8

=> FIL HOME  
COST IN U.S. DOLLARS

SINCE FILE	TOTAL
ENTRY	SESSION
5.25	66.38

FULL ESTIMATED COST

FILE 'HOME' ENTERED AT 16:03:21 ON 10 JUN 2003

=> file reg

COST IN U.S. DOLLARS

SINCE FILE	TOTAL
------------	-------

	ENTRY	SESSION
FULL ESTIMATED COST	1.89	68.27

FILE 'REGISTRY' ENTERED AT 16:08:51 ON 10 JUN 2003  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
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STRUCTURE FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8  
DICTIONARY FILE UPDATES: 9 JUN 2003 HIGHEST RN 528266-88-8

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 6, 2003

Please note that search-term pricing does apply when  
conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. See HELP  
PROPERTIES for more information. See STNote 27, Searching Properties  
in the CAS Registry File, for complete details:  
<http://www.cas.org/ONLINE/STN/STNOTES/stnotes27.pdf>

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 963 AND 1006

L10 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\09940665.str

L11 STRUCTURE UPLOADED

=> que L11 AND L10

L12 QUE L11 AND L10

=> d

L12 HAS NO ANSWERS

L10 SCR 963 AND 1006

L11 STR

\*\*\* STRUCTURE DIAGRAM IS NOT AVAILABLE \*\*\*

Structure attributes must be viewed using STN Express query preparation.

L12 QUE ABB=ON PLU=ON L11 AND L10

=> s l12

SAMPLE SEARCH INITIATED 16:09:15 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 28 TO ITERATE

100.0% PROCESSED 28 ITERATIONS  
SEARCH TIME: 00.00.01

0 ANSWERS

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*

PROJECTED ITERATIONS: 243 TO 877  
PROJECTED ANSWERS: 0 TO 0

L13 0 SEA SSS SAM L11 AND L10

=> s l12 sss sam

SAMPLE SEARCH INITIATED 16:09:19 FILE 'REGISTRY'  
SAMPLE SCREEN SEARCH COMPLETED - 28 TO ITERATE

100.0% PROCESSED 28 ITERATIONS 0 ANSWERS  
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*

PROJECTED ITERATIONS: 243 TO 877  
PROJECTED ANSWERS: 0 TO 0

L14 0 SEA SSS SAM L11 AND L10

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.40	68.67

FILE 'CAPLUS' ENTERED AT 16:09:23 ON 10 JUN 2003  
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FILE 'HCAPLUS' ENTERED AT 16:09:23 ON 10 JUN 2003  
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FILE 'USPATFULL' ENTERED AT 16:09:23 ON 10 JUN 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPAT2' ENTERED AT 16:09:23 ON 10 JUN 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l14

L15 0 L14

=> d his

(FILE 'HOME' ENTERED AT 15:58:22 ON 10 JUN 2003)

FILE 'REGISTRY' ENTERED AT 15:58:43 ON 10 JUN 2003

L1 0 S GAMMA-BUTYROLACTONE  
L2 422 S GAMMA-BUTYROLACTONE

FILE 'REGISTRY' ENTERED AT 16:00:16 ON 10 JUN 2003

L3 STR 195000-66-9  
L4 0 S L3 EXA SAM

FILE 'REGISTRY' ENTERED AT 16:00:32 ON 10 JUN 2003

L5 1 S 195000-66-9/RN  
SET NOTICE 1 DISPLAY  
SET NOTICE LOGIN DISPLAY

FILE 'REGISTRY' ENTERED AT 16:01:26 ON 10 JUN 2003

FILE 'REGISTRY' ENTERED AT 16:02:03 ON 10 JUN 2003  
L6 2 S GAMMA-BUTYROLACTONE METHACRYLATE

L7 7 S 2-METHYLADAMANTYL METHACRYLATE  
L8 1 S L6 AND L7

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 16:03:03 ON 10 JUN 2003

L9 95 S L8

FILE 'HOME' ENTERED AT 16:03:21 ON 10 JUN 2003

FILE 'REGISTRY' ENTERED AT 16:08:51 ON 10 JUN 2003

L10 SCREEN 963 AND 1006

L11 STRUCTURE UPLOADED

L12 QUE L11 AND L10

L13 0 S L12

L14 0 S L12 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 16:09:23 ON 10 JUN 2003

L15 0 S L14

=> s l9 and l15

L16 0 L9 AND L15

=> s l9 and (resist or photoresist)

L17 95 L9 AND (RESIST OR PHOTORESIST)

=> s l17 and (?acid generator)

L18 77 L17 AND (?ACID GENERATOR)

=> s (?5active)

L19 7 (?5ACTIVE)

=> s l18 and acetal

L20 12 L18 AND ACETAL

=> duplicates remove

ENTER L# LIST OR (END):l20

DUPLICATE PREFERENCE IS 'CAPLUS, HCAPLUS, USPATFULL, USPAT2'

KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n

PROCESSING COMPLETED FOR L20

L21 8 DUPLICATE REMOVE L20 (4 DUPLICATES REMOVED)

=> d l21 1-8 ibib abs hitstr

L21 ANSWER 1 OF 8 USPATFULL

ACCESSION NUMBER: 2003:120442 USPATFULL

TITLE: Pattern formation method

INVENTOR(S): Endo, Masayuki, Osaka, JAPAN

Sasago, Masaru, Osaka, JAPAN

PATENT ASSIGNEE(S): Matsushita Electric Industrial Co., Ltd., Osaka, JAPAN,  
571-8501 (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003082926	A1	20030501
APPLICATION INFO.:	US 2002-279070	A1	20021024 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-334168	20011031
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	NIXON PEABODY, LLP, 8180 GREENSBORO DRIVE, SUITE 800, MCLEAN, VA, 22102	

10-04-02

NUMBER OF CLAIMS: 12  
EXEMPLARY CLAIM: 1  
NUMBER OF DRAWINGS: 3 Drawing Page(s)  
LINE COUNT: 715  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A **resist** film is formed from a chemically amplified **resist** material including a base polymer having a protecting group released by a function of an acid, an acrylic compound and an **acid generator** that generates an acid when irradiated with light. The **resist** film is selectively irradiated with exposing light for pattern exposure, and is developed after the pattern exposure so as to form a **resist** pattern having a hole or groove opening. The size of the opening is reduced by irradiating the **resist** pattern with light with annealing.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 195000-67-0

(pattern formation method contg.)

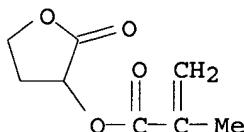
RN 195000-67-0 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 195000-66-9

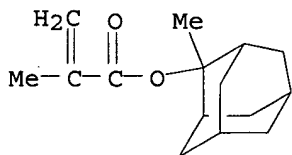
CMF C8 H10 O4



CM 2

CRN 177080-67-0

CMF C15 H22 O2



L21 ANSWER 2 OF 8 CAPLUS COPYRIGHT 2003 ACS

DUPLICATE 1

ACCESSION NUMBER: 2002:794184 CAPLUS

DOCUMENT NUMBER: 137:317925

TITLE: Chemically amplified **resist** composition and method for forming patterned film using same

INVENTOR(S): Yamamoto, Hajime; Murakami, Kenichi; Takechi, Satoshi

PATENT ASSIGNEE(S): Fujitsu Limited, Japan

SOURCE: U.S. Pat. Appl. Publ., 10 pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2002150834	A1	20021017	US 2001-940665 →	20010829
JP 2002311587	A2	20021023	JP 2001-111740	20010410
DE 10147011	A1	20021107	DE 2001-10147011	20010925

*present  
appl.*

PRIORITY APPLN. INFO.:

JP 2001-111740 A 20010410

AB The present invention relates to a chem. amplified **resist** compn. which comprises (1) a base resin reacting in the presence of an acid, (2) a photo **acid generator** generating an acid upon exposure, and (3) a compd. having the combination of an **acetal** moiety and a site which is eliminated by an acid in its mol., or which comprises (1) a base resin, which is a copolymer having the combination of an **acetal** moiety and a site eliminated by an acid in one repeating unit and reacts in the presence of an acid, and (2) a photo **acid generator** generating an acid upon exposure. The present invention relates to a chem. amplified **resist** compn., which is a radiation-sensitive material used in the manuf. of semiconductor devices, and method for forming a patterned film using the **resist** compn.

IT 195000-67-0

RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)

(chem. amplified **photoresist** compn. for lithog. patterning contg.)

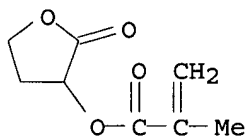
RN 195000-67-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 195000-66-9

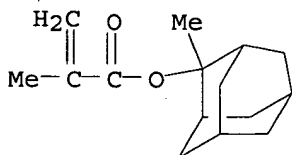
CMF C8 H10 O4



CM 2

CRN 177080-67-0

CMF C15 H22 O2



L21 ANSWER 3 OF 8 USPATFULL

DUPLICATE 2

ACCESSION NUMBER: 2002:156925 USPATFULL

TITLE: Chemical amplification type positive **resist** composition



INVENTOR(S): Uetani, Yasunori, Osaka, JAPAN  
Inoue, Hiroki, Osaka, JAPAN  
PATENT ASSIGNEE(S): Sumitomo Chemical Co., Ltd. (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2002081523	A1	20020627
	US 6548221	B2	20030415
APPLICATION INFO.:	US 2001-3441	A1	20011206 (10)
RELATED APPLN. INFO.:	Division of Ser. No. US 2000-482359, filed on 14 Jan 2000, PENDING *		

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-9096	19990118
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	BIRCH STEWART KOLASCH & BIRCH, PO BOX 747, FALLS CHURCH, VA, 22040-0747	
NUMBER OF CLAIMS:	8	
EXEMPLARY CLAIM:	1	
LINE COUNT:	788	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A positive **resist** composition is provided which comprises a resin having 2-alkyl-2-adamantyl (meth)acrylate polymerization unit represented by the following formula (I): ##STR1##

wherein R.<sup>sup.1</sup> represents hydrogen or methyl and R.<sup>sup.2</sup> represents an alkyl, and being insoluble or barely soluble in alkali, but being converted to soluble in alkali by the action of an and an **acid generator** represented by the following formula (V): ##STR2##

wherein Q.<sup>sup.1</sup>, Q.<sup>sup.2</sup> and Q.<sup>sup.3</sup> independently represent hydrogen, a hydroxyl group, an alkyl having 1 to 6 carbon atoms or an alkoxy having 1 to 6 carbon atoms, and n is an integer of 4 to 8; and gives a good resolution upon exposure by ArP excimer laser and has little substrate dependency.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 195000-67-0P

(chem. amplification-type pos. resist compn.)

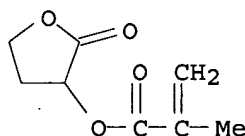
RN 195000-67-0 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 195000-66-9

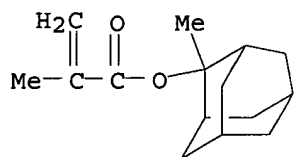
CMF C8 H10 O4



CM 2

CRN 177080-67-0

CMF C15 H22 O2



L21 ANSWER 4 OF 8 USPATFULL

DUPLICATE 3

ACCESSION NUMBER: 2002:99037 USPATFULL  
 TITLE: Positive photosensitive composition  
 INVENTOR(S): Kodama, Kunihiro, Shizuoka, JAPAN  
 Aoi, Toshiaki, Shizuoka, JAPAN  
 PATENT ASSIGNEE(S): FUJI PHOTO FILM CO., LTD. (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2002051933	A1	20020502
	US 6492091	B2	20021210
APPLICATION INFO.:	US 2001-921691	A1	20010806

(9) 8-6-01

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2000-240059	20000808
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	SUGHRUE, MION, ZINN, MACPEAK & SEAS, PLLC, 2100 Pennsylvania Avenue, N.W., Washington, DC, 20037	
NUMBER OF CLAIMS:	20	
EXEMPLARY CLAIM:	1	
LINE COUNT:	2260	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A positive photosensitive composition comprises: (A) a compound generating an acid upon irradiation with one of an actinic ray and radiation; (B) a resin containing a monocyclic or polycyclic alicyclic hydrocarbon structure and increasing the solubility to an alkali developer by the action of an acid; and (C) an onium salt of carboxylic acid.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 195000-67-0P

(resin; deep UV photofabrication pos. photoresist compn. contg.)

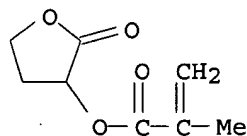
RN 195000-67-0 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 195000-66-9

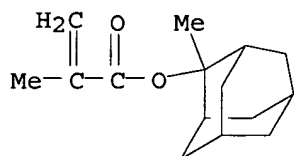
CMF C8 H10 O4



CM 2

CRN 177080-67-0

CMF C15 H22 O2



L21 ANSWER 5 OF 8 USPATFULL

ACCESSION NUMBER: 2002:191427 USPATFULL

TITLE: Positive photosensitive composition

INVENTOR(S): Kodama, Kunihiro, Shizuoka, JAPAN

Aoi, Toshiaki, Shizuoka, JAPAN

PATENT ASSIGNEE(S): FUJI PHOTO FILM CO., LTD. (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2002102491	A1	20020801
APPLICATION INFO.:	US 2001-978103	A1	20011017 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2000-321128	20001020
	JP 2000-352899	20001120
	JP 2001-132546	20010427

DOCUMENT TYPE: Utility

FILE SEGMENT: APPLICATION

LEGAL REPRESENTATIVE: SUGHRUE, MION, ZINN, MACPEAK & SEAS, PLLC, 2100  
Pennsylvania Avenue, N.W., Washington, DC, 20037

NUMBER OF CLAIMS: 18

EXEMPLARY CLAIM: 1

LINE COUNT: 2767

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A positive photosensitive composition comprises a compound capable of generating a specified sulfonic acid upon irradiation with one of an actinic ray and radiation and (B) a resin capable of decomposing under the action of an acid to increase the solubility in an alkali developer.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 195000-67-0

(photo-acid generator used in pos. photoresist compn.)

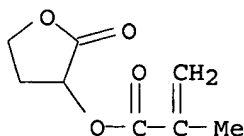
RN 195000-67-0 USPATFULL

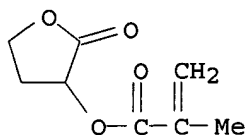
CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 195000-66-9

CMF C8 H10 O4

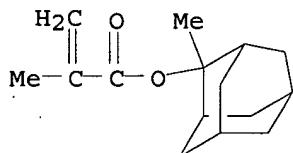




CM 2

CRN 177080-67-0

CMF C15 H22 O2



L21 ANSWER 6 OF 8 USPATFULL

ACCESSION NUMBER: 2002:102236 USPATFULL

TITLE: Chemical amplification type positive **resist** composition

INVENTOR(S): Uetani, Yasunori, Toyonaka, JAPAN

Inoue, Hiroki, Toyonaka, JAPAN

PATENT ASSIGNEE(S): Sumitomo Chemical Company, Limited, Osaka, JAPAN  
(non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6383713	B1	20020507
APPLICATION INFO.:	US 2000-482359		20000114 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-9096	19990118
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Ashton, Rosemary	
LEGAL REPRESENTATIVE:	Birch Stewart Kolasch & Birch LLP	
NUMBER OF CLAIMS:	2	
EXEMPLARY CLAIM:	1	
NUMBER OF DRAWINGS:	0 Drawing Figure(s); 0 Drawing Page(s)	
LINE COUNT:	776	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A positive **resist** composition is provided which comprises a resin having 2-alkyl-2-adamantyl (meth)acrylate polymerization unit represented by the following formula (I): ##STR1##

wherein R.<sup>sup.1</sup> represents hydrogen or methyl and R.<sup>sup.2</sup> represents an alkyl, and being insoluble or barely soluble in alkali, but being converted to soluble in alkali by the action of an acid;

and an **acid generator** represented by the following formula (V): ##STR2##

wherein Q.<sup>sup.1</sup>, Q.<sup>sup.2</sup> and Q.<sup>sup.3</sup> independently represent hydrogen, a hydroxyl group, an alkyl having 1 to 6 carbon atoms or an alkoxy having 1 to 6 carbon atoms, and n is an integer of 4 to 8. The composition exhibits good resolution upon exposure by a ArP excimer laser and has

little substrate dependency.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 195000-67-0P

(chem. amplification-type pos. resist compn.)

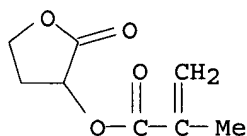
RN 195000-67-0 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl ester,  
polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA  
INDEX NAME)

CM 1

CRN 195000-66-9

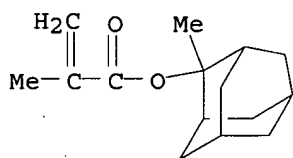
CMF C8 H10 O4



CM 2

CRN 177080-67-0

CMF C15 H22 O2



L21 ANSWER 7 OF 8 USPATFULL

ACCESSION NUMBER: 2002:34281 USPATFULL

TITLE: Chemical amplification type positive **resist**

INVENTOR(S): Uetani, Yasunori, Toyonaka, JAPAN

Oohashi, Kenji, Yawata, JAPAN

Inoue, Hiroki, Toyonaka, JAPAN

PATENT ASSIGNEE(S): Sumitomo Chemical Company, Limited, Osaka, JAPAN  
(non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6348297	B1	20020219
APPLICATION INFO.:	US 2000-533986		20000324 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-92990	19990331
	JP 1999-315264	19991105
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Ashton, Rosemary	
LEGAL REPRESENTATIVE:	Birch, Stewart, Kolasch & Birch, LLP	
NUMBER OF CLAIMS:	16	
EXEMPLARY CLAIM:	1	
NUMBER OF DRAWINGS:	0 Drawing Figure(s); 0 Drawing Page(s)	

LINE COUNT: 1138

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A chemical amplification type positive **resist** composition which is good in resolution, provide a good pattern profile under exposure using light of wavelength of 220 nm or shorter even when applied on a basic substrate or a low reflectance substrate and which comprises an **acid generator** comprising an aliphatic sulfonium salt represented by the following formula (I): ##STR1##

wherein Q.sup.1 represents an alkyl group, Q.sup.2 represents an alkyl or a residue of an alicyclic hydrocarbon and m represents an integer of 1 to 8; and onium salt selected from triphenylsulfonium salts represented by the following formula (IIa) and diphenyliodonium salts represented by the following formula (IIb): ##STR2##

wherein Q.sup.3, Q.sup.4, Q.sup.5, Q.sup.6 and Q.sup.7 each independently represent a hydrogen atom, a hydroxyl group, an alkyl group having 1 to 6 carbon atoms, an alkoxy group having 1 to 6 carbon atoms, and q and p represent an integer of 4 to 8; and (2) a resin which has a polymerization unit with a group unstable to an acid, and is insoluble or barely soluble in alkali by itself but changes soluble in alkali by an action of the acid, is provided.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 195000-67-0P, .alpha.-Methacryloyloxy-.gamma.-butyrolactone-2-methyl-2-adamantyl methacrylate copolymer  
(manuf. of resin for chem.-amplified pos. resist contg.)

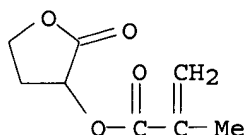
RN 195000-67-0 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.3<sup>2,7</sup>]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 195000-66-9

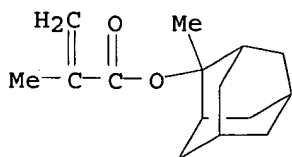
CMF C8 H10 O4



CM 2

CRN 177080-67-0

CMF C15 H22 O2



L21 ANSWER 8 OF 8 USPATFULL

ACCESSION NUMBER: 2001:79255 USPATFULL

TITLE: Chemical amplifying type positive **resist**

composition  
 INVENTOR(S): Fujishima, Hiroaki, Toyonaka, Japan  
 Uetani, Yasunori, Toyonaka, Japan  
 Araki, Karou, Kyoto, Japan  
 PATENT ASSIGNEE(S): Sumitomo Chemical, Company Limited, Osaka, Japan  
 (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6239231	B1	20010529
APPLICATION INFO.:	US 1999-384032		19990826 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1998-240143	19980826
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	Granted	
PRIMARY EXAMINER:	Lipman, Bernard	
LEGAL REPRESENTATIVE:	Birch, Stewart, Kolasch & Birch, LLP	
NUMBER OF CLAIMS:	16	
EXEMPLARY CLAIM:	1	
LINE COUNT:	860	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

AB A chemical amplifying type positive **resist** composition, excellent in adhesion to a substrate and good in **resist** performances and suitable for exposure using a KrF excimer laser, ArF excimer laser, or the like, which comprises a resin having a polymerization unit of 2-alkyl-2-adamantyl (meth)acrylate and a polymerization unit of a monomer selected from 3-hydroxy-1-adamantyl (meth)acrylate and (meth)acrylonitrile, and an **acid generator** is provided.

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 195000-67-0P

(prepn. and use in prepg. chem. amplified pos. photoresists)

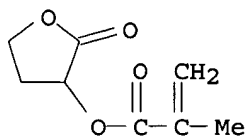
RN 195000-67-0 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 195000-66-9

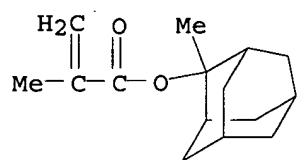
CMF C8 H10 O4



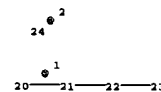
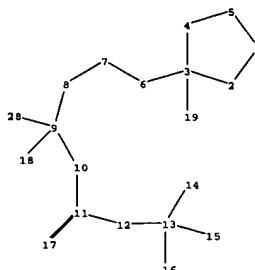
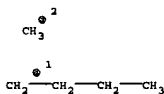
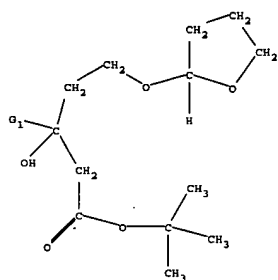
CM 2

CRN 177080-67-0

CMF C15 H22 O2







structure searched

chain nodes :

6 7 8 9 10 11 12 13 14 15 16 17 18 19 20 21 22 23 24 28

ring nodes :

1 2 3 4 5

chain bonds :

3-6 3-19 6-7 7-8 8-9 9-10 9-18 9-28 10-11 11-12 11-17 12-13 13-14 13-15 13-16  
20-21 21-22 22-23

ring bonds :

1-2 1-5 2-3 3-4 4-5

exact/norm bonds :

1-2 1-5 2-3 3-4 3-6 4-5 9-18 9-28 11-12 11-17 12-13

exact bonds :

3-19 6-7 7-8 8-9 9-10 10-11 13-14 13-15 13-16 20-21 21-22 22-23

G1:[\*1],[\*2]

Match level :

1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:CLASS 7:CLASS 8:CLASS 9:CLASS 10:CLASS  
11:CLASS 12:CLASS 13:CLASS 14:CLASS 15:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS  
20:CLASS 21:CLASS 22:CLASS 23:CLASS 24:CLASS 28:CLASS

=>  
Uploading C:\Program Files\Stnexp\Queries\09940665.str

L22        STRUCTURE UPLOADED

=> que L22

L23    QUE L22

=> d  
L23 HAS NO ANSWERS  
L22                STR

\*\*\* STRUCTURE DIAGRAM IS NOT AVAILABLE \*\*\*

Structure attributes must be viewed using STN Express query preparation.  
L23                QUE    ABB=ON    PLU=ON    L22

=> s l23 sss sam  
SAMPLE SEARCH INITIATED 16:13:24 FILE 'REGISTRY'  
SAMPLE SCREEN SEARCH COMPLETED -        35 TO ITERATE

100.0% PROCESSED        35 ITERATIONS                                0 ANSWERS  
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS:    ONLINE    \*\*COMPLETE\*\*  
                              BATCH    \*\*COMPLETE\*\*  
PROJECTED ITERATIONS:        346 TO        1054  
PROJECTED ANSWERS:                0 TO        0

L24                0 SEA SSS SAM L22

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2  
COST IN U.S. DOLLARS                                SINCE FILE        TOTAL  
    ENTRY        SESSION  
FULL ESTIMATED COST                                0.40        126.12  
  
DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)        SINCE FILE        TOTAL  
    ENTRY        SESSION  
CA SUBSCRIBER PRICE                                0.00        -0.65

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=> s l24  
L25                0 L24